Application No. 10/049,615
'Amendment dated July 13, 2004
Reply to Office Action of April 21, 2004

## Amendments to the Claims

This listing of claims will replace all prior versions, and listings, of claims in the application:

## **Listing of Claims:**

1. (Currently Amended): A ferromagnetic p-type single-crystal zinc oxide material consisting essentially of: comprising a single-crystal of zinc oxide that contains

1 to 99 mol% manganese,

a p-type dopant selected from a group consisting of C, N, and oxides thereof, and the balance p type single-crystal zinc oxide,

wherein said p-type single-crystal zinc oxide material having a hole concentration of 1  $\times$  10<sup>18</sup> cm<sup>-3</sup> or more and a low resistance of 1  $\Omega$  · cm or less.

2. (Currently Amended): A ferromagnetic p-type single-crystal zinc oxide material consisting essentially of: comprising a single-crystal of zinc oxide that contains

1 to 99 mol% manganese,

a p-type dopant selected from a group consisting of C, N, and oxides thereof,

an n-type dopant selected from a group consisting of B, Al, In, Ga, Zn, and oxides thereof,

and

the balance p-type single-crystal zinc oxide,

wherein said p-type single-crystal zinc oxide material having a hole concentration of 1  $\times$  10<sup>18</sup> cm<sup>-3</sup> or more and a low resistance of 1  $\Omega$  · cm or less.

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3. (Currently Amended): A method for manufacturing a ferromagnetic p-type single-crystal

zinc oxide material comprising steps of:

holding a semiconductor substrate within a temperature range of 300-800 °C in a vacuum

atmosphere of about 10<sup>-8</sup> Torr;

supplying an atomic gas from a solid-state source of Zn or Zn oxide and an activated

oxygen onto a said semiconductor substrate to grow a single-crystal zinc-oxide thin film on the

substrate while an atomic p-type dopant selected from a group consisting of C, N, and oxides

thereof and an atomic Mn are supplied all together onto the substrate at a partial pressure of about

 $5x10^{-7}$ .

4. (Currently Amended): A method as defined in claim 3, further comprising a step of

doping [[the]] an n-type dopant so as to provide a higher concentration of the p-type dopant than

that of the n-type dopant.

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